

PATTERN FOR IMPROVED VISUAL INSPECTION
OF SEMICONDUCTOR DEVICES

ABSTRACT OF THE DISCLOSURE

5 A semiconductor structure is disclosed that enhances quality control inspection of
device. The structure includes a substrate having at least one planar face, a first metal layer
on the planar face, and covering some, but not all of the planar face in a first predetermined
geometric pattern, and a second metal layer on the planar face, and covering some, but not all
of the planar face in a second geometric pattern that is different from the first geometric
10 pattern. A quality control method for manufacturing a semiconductor device is also
disclosed. The method includes the steps of placing a first metal layer on a semiconductor
face of a device in a first predetermined geometric pattern, placing a second metal layer on
the same face of the device as the first layer and in a second predetermined geometric pattern
that is different from the first geometric pattern, and then inspecting the device to identify the
15 presence or absence of one or both of the patterns on the face.

\\SERVER\C\FIRM DOCS\5000\142\SPEC142.DOC